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INFORMATION DISCLOSURE  
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## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Sub-Class	Filing Date, If Appropriate
	4,828,080	Jun. 1977	Di Vita		
	4,157,253	Jun. 1979	Hemquist		
	4,182,664	Jan. 1980	Maklad		
	5,267,343	Nov. 1993	Lyons		
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## FOREIGN PATENT DOCUMENTS

Examiner Initials	Document Number	Date	Country	Sub-Class	Class	Translation Yes No
	0 887 924 A1	Dec. 20, 1995	EPO			
	2808457	Aug. 1974	Germany			
	4-342427	Nov. 1992	Japan			(To follow)
	4-342436	Nov. 1992	Japan			(To follow)
	6-199539	Jun. 7, 1994	Japan			
	52-94657	Nov. 1993	Japan			
	54-134721	Oct. 1979	Japan			
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	57-191247	Nov. 25, 1982	Japan			
	60-200204	Oct. 9, 1985	Japan			
	61-45201	Mar. 5, 1986	Japan			
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"Thermal Annealing of Defects Induced by ArF Excimer Laser Irradiation in a SiO<sub>2</sub>," Japanese Society of Applied Physics, Catalog No. AP 90110-02 (English Translation) (To follow)

ROTHSCHILD, Mordechai, Daniel J. EHRLICH and David C. SHAVER, "Excimer Laser Induced Damage in Fused Silica", *Microelectronic Engineering* 11, 1990, pp. 167-172.

"Temperature Dependence of the E' Center Creation in Silica Glasses", *Physica Status Solidi (b)*, vol. 147, No. 1, 1988, pp. k1-k4.

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